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(12) **United States Design Patent**
Han et al.

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(45) **Date of Patent: ** Aug. 13, 2024**

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(54) **FACE MASK**

(71) Applicant: **Honeywell International Inc.**, Charlotte, NC (US)

(72) Inventors: **Xiaojin Han**, Shanghai (CN); **Seven Zhou**, Shanghai (CN); **Hongbing Xiang**, Shanghai (CN); **Weifeng Shen**, Shanghai (CN); **Xia Jin Zhao**, Shanghai (CN); **Teicheng Qu**, Shanghai (CN)

(73) Assignee: **HONEYWELL INTERNATIONAL INC.**, Charlotte, NC (US)

(**) Term: **15 Years**

(21) Appl. No.: **29/803,436**

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(51) **LOC (14) Cl.** **29-02**

(52) **U.S. Cl.**
USPC **D24/110.1**; D29/108

(58) **Field of Classification Search**
USPC D24/110, 110.1–110.6; D29/108
CPC . A41D 13/11; A41D 13/1107; A41D 13/1115; A41D 13/1123; A41D 13/113; A41D 13/1138; A41D 13/1146; A41D 13/1153; A41D 13/1161; A41D 13/1169; A41D 13/1176; A41D 13/1184; A61M 16/06; A62B 18/00; A62B 18/02; A62B 18/025; A62B 23/00
See application file for complete search history.

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Primary Examiner — Richard Kearney
Assistant Examiner — Michael Hoffman
(74) *Attorney, Agent, or Firm* — ALSTON & BIRD LLP

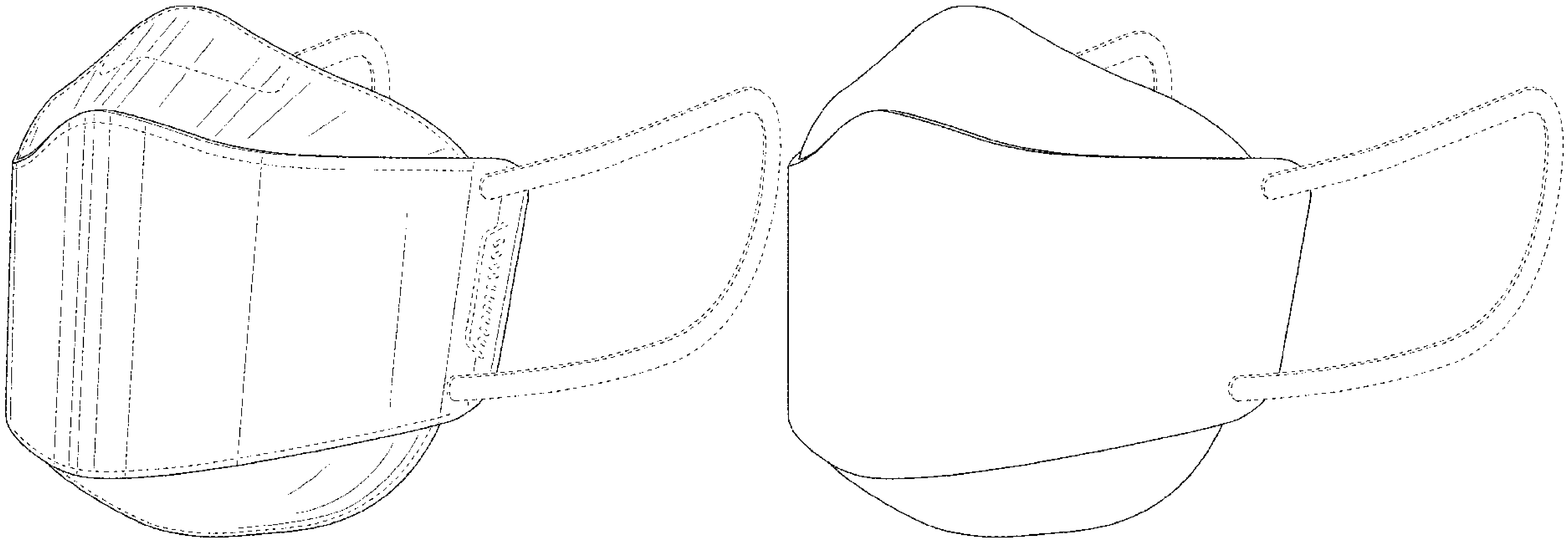
(57) **CLAIM**

We claim the ornamental design for a face mask, as shown and described.

DESCRIPTION

FIG. **1** is a perspective view of an embodiment of a face mask showing the new design;
FIG. **2** is a front elevation view thereof;
FIG. **3** is a rear elevation view thereof;
FIG. **4** is a right side elevation view thereof;
FIG. **5** is a left side elevation view thereof;
FIG. **6** is a top plan view thereof; and
FIG. **7** is a bottom plan view thereof.
FIG. **8** is a perspective view of another embodiment of a face mask showing the new design;
FIG. **9** is a front elevation view thereof;
FIG. **10** is a rear elevation view thereof;
FIG. **11** is a right side elevation view thereof;
FIG. **12** is a left side elevation view thereof;
FIG. **13** is a top plan view thereof; and,
FIG. **14** is a bottom plan view thereof.
The broken lines illustrate portions of the face mask that form no part of the claimed design.

1 Claim, 12 Drawing Sheets



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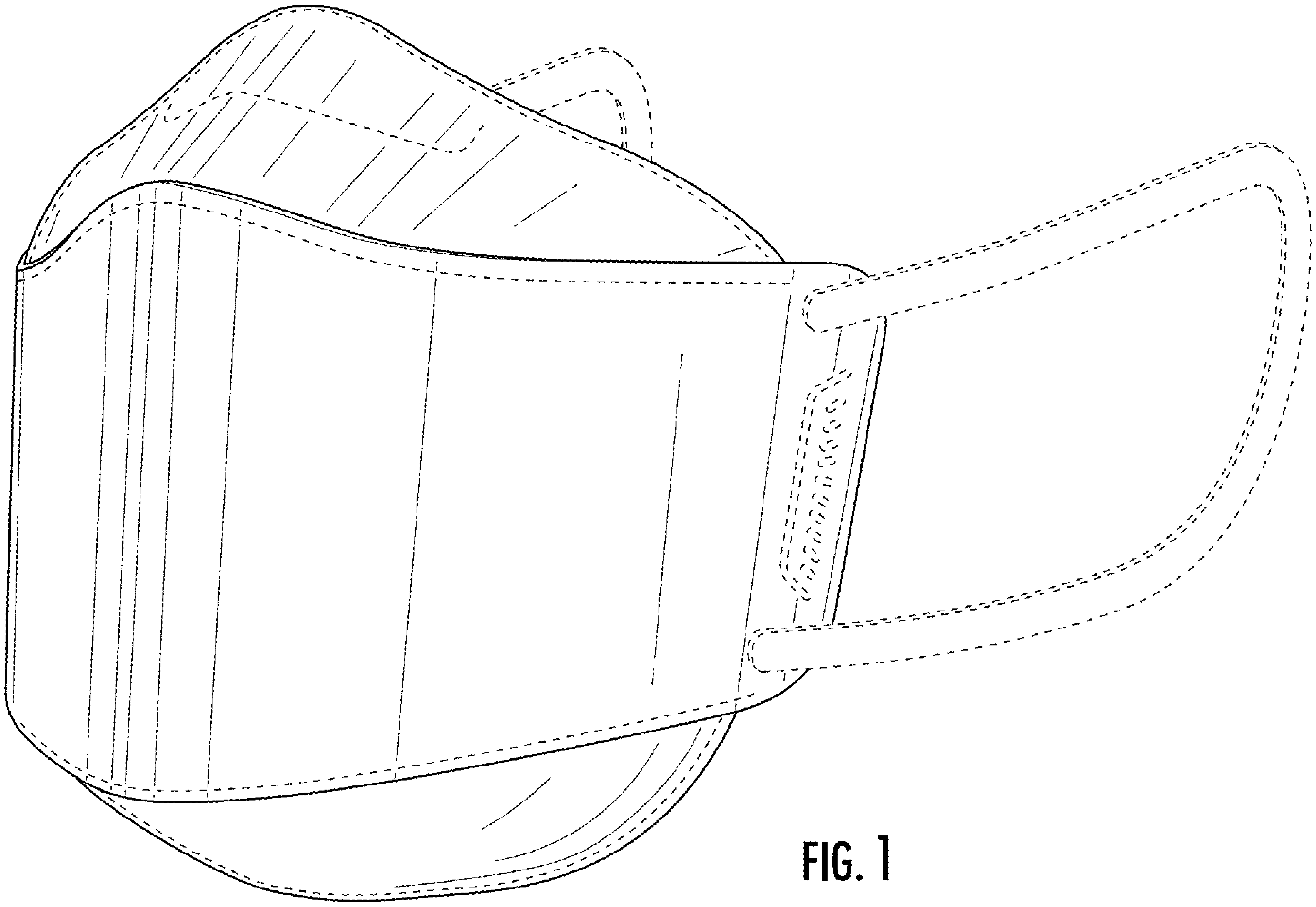

FIG. 1

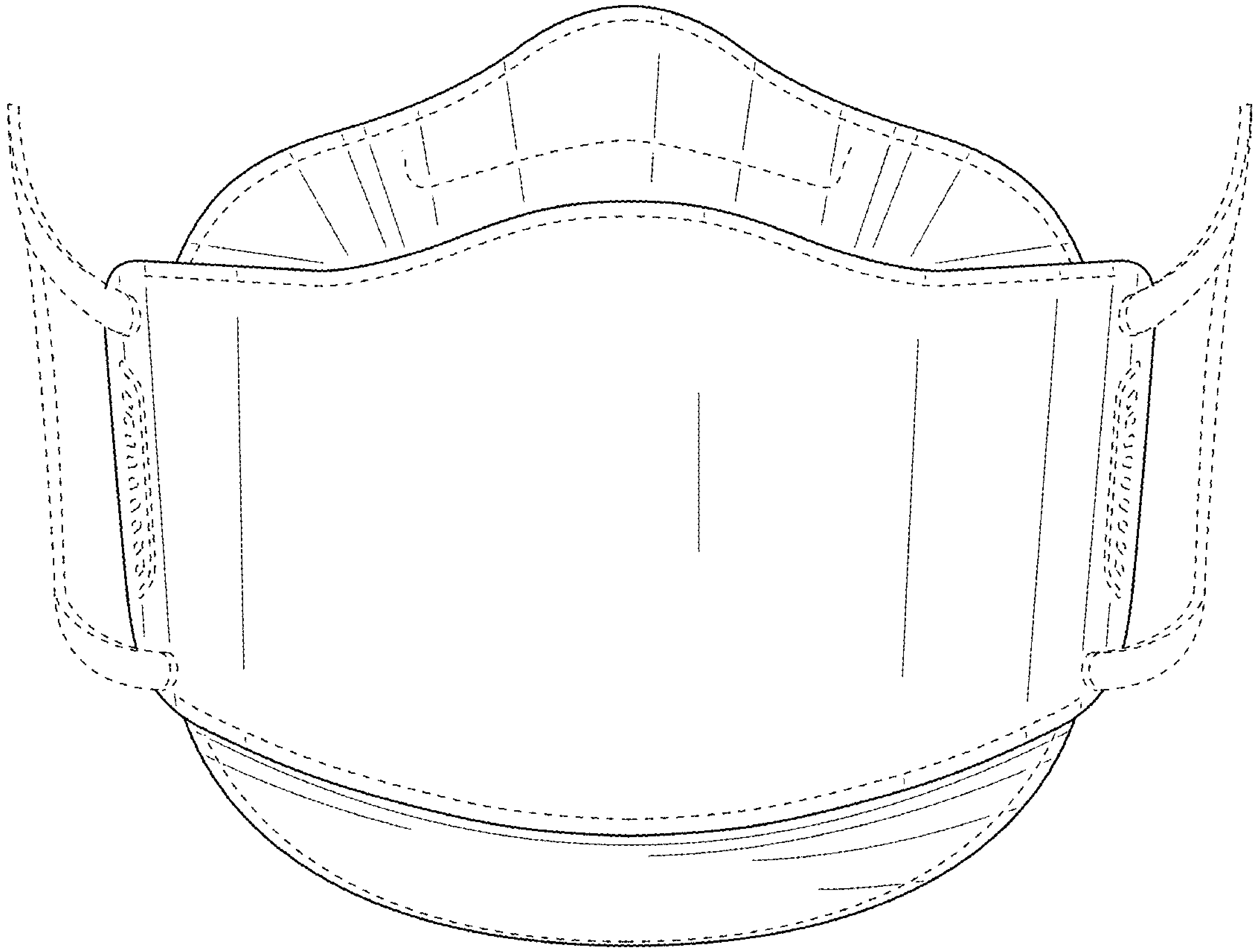

FIG. 2

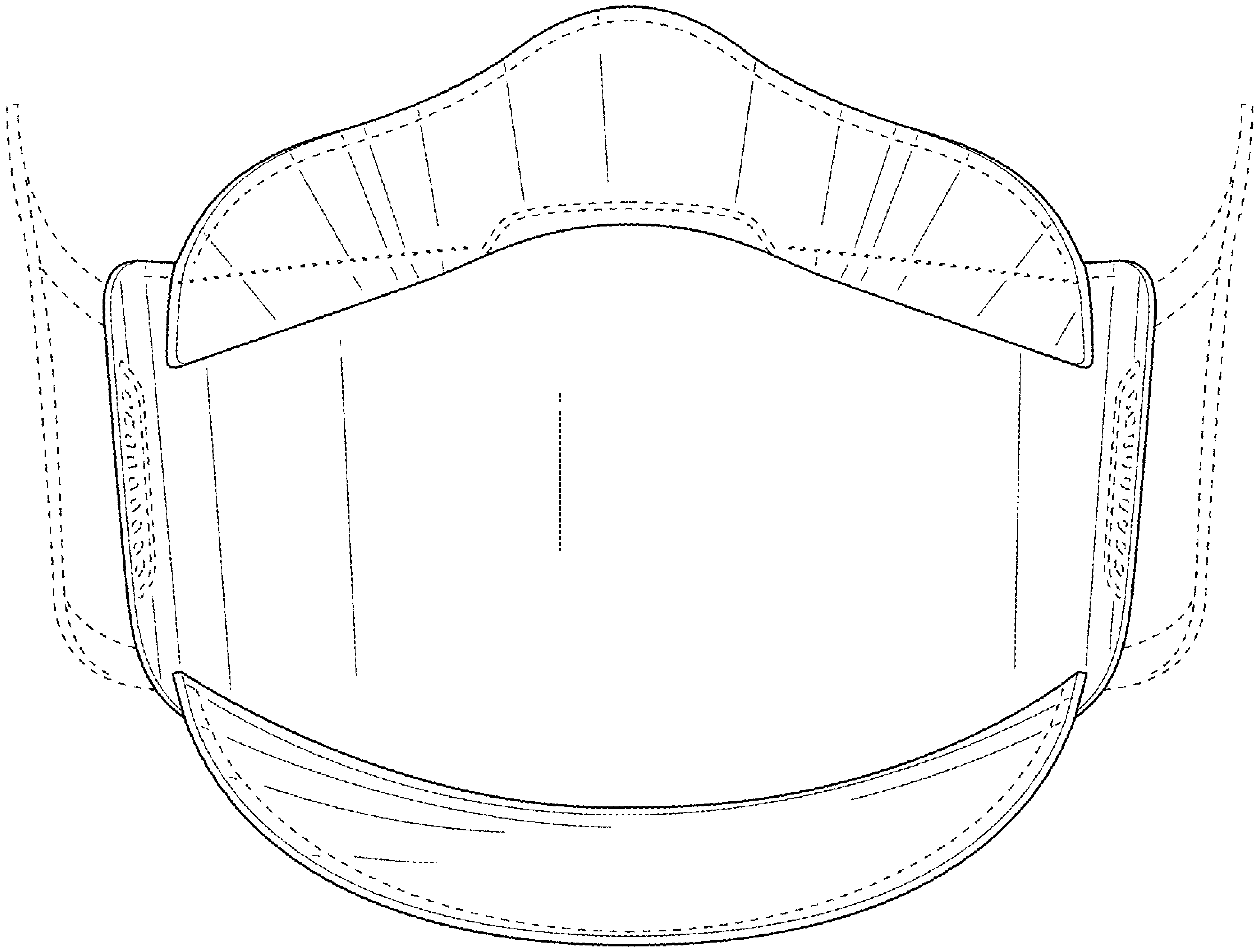

FIG. 3

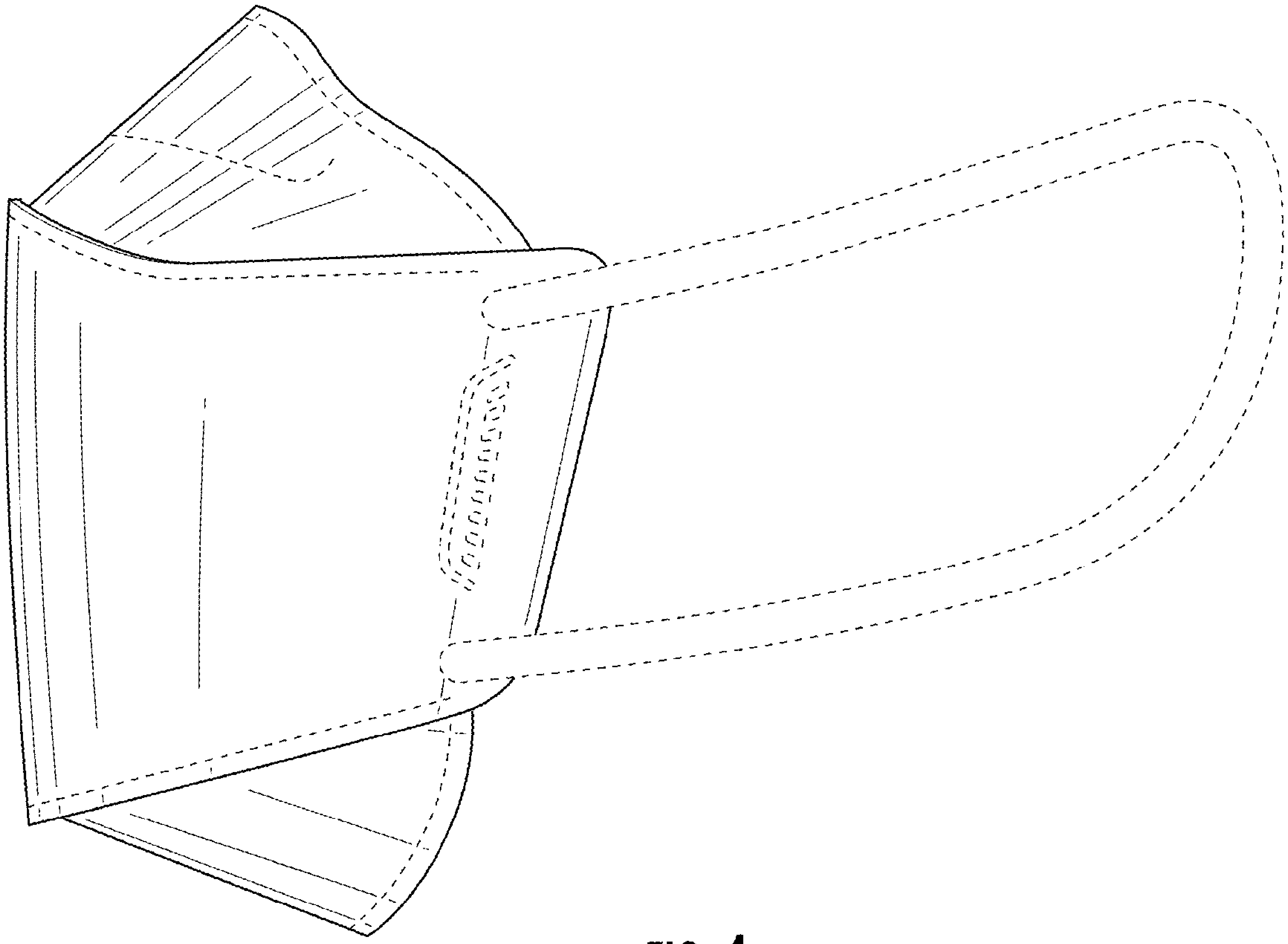

FIG. 4

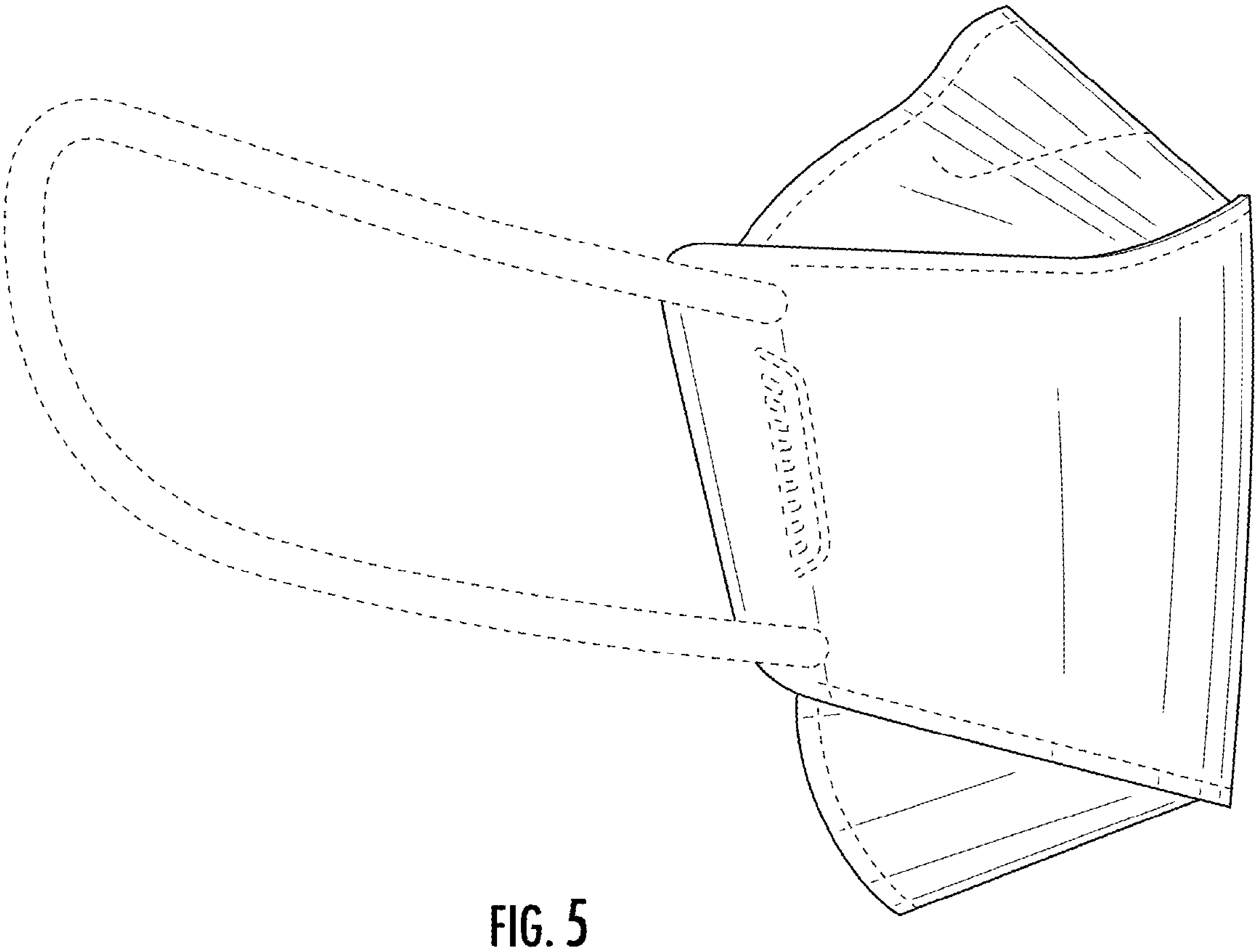

FIG. 5

FIG. 6

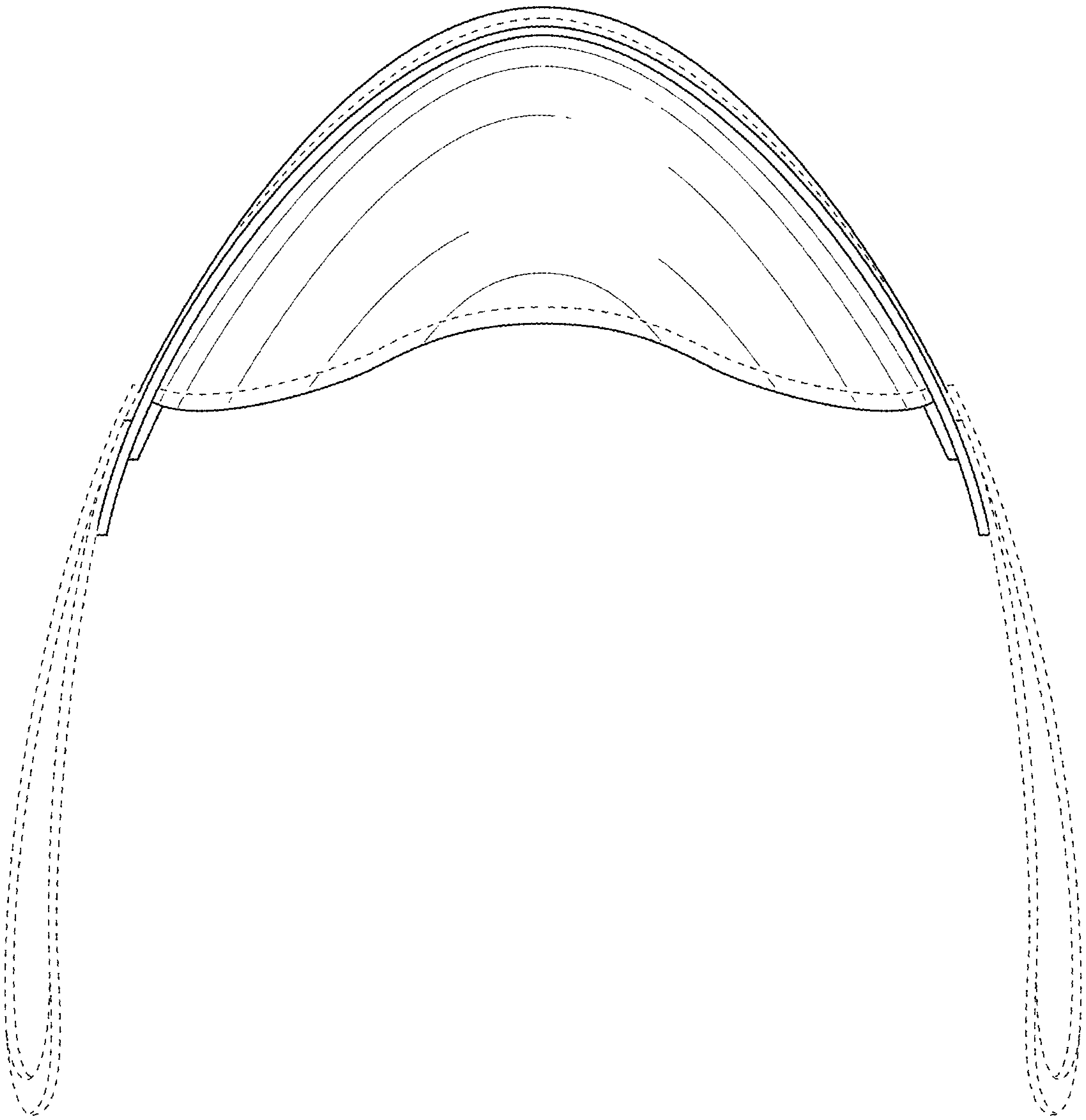

FIG. 7

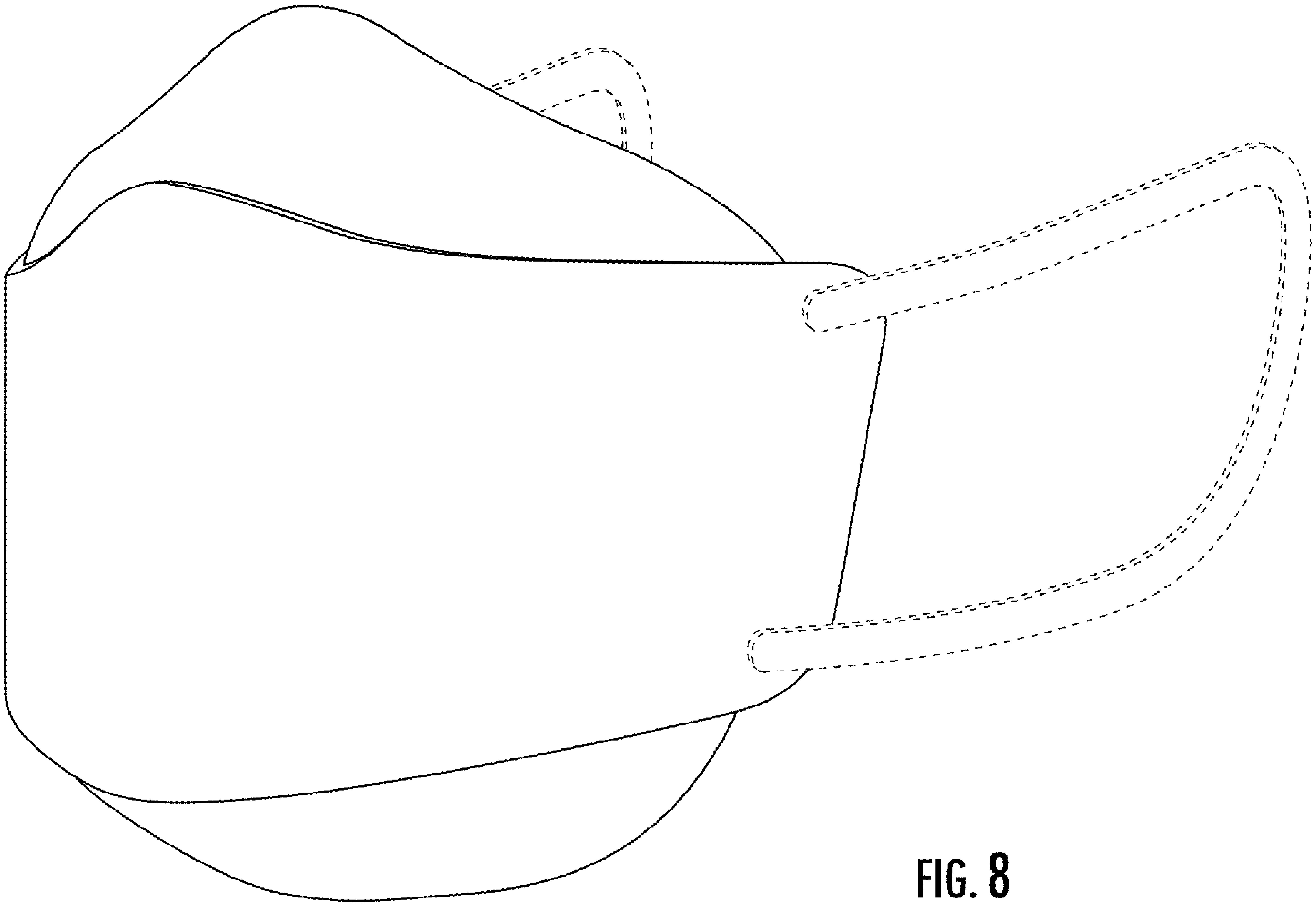

FIG. 8

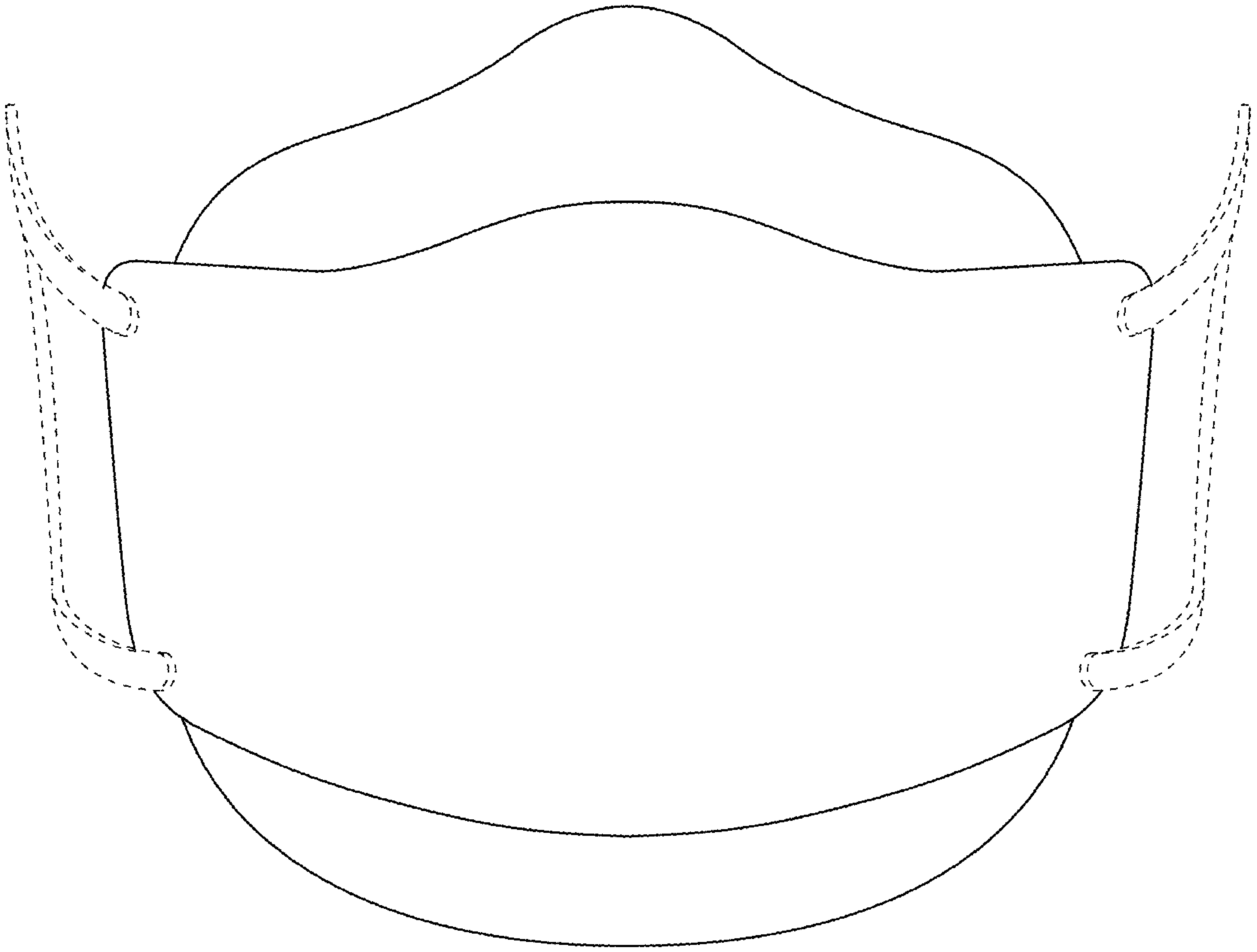

FIG. 9

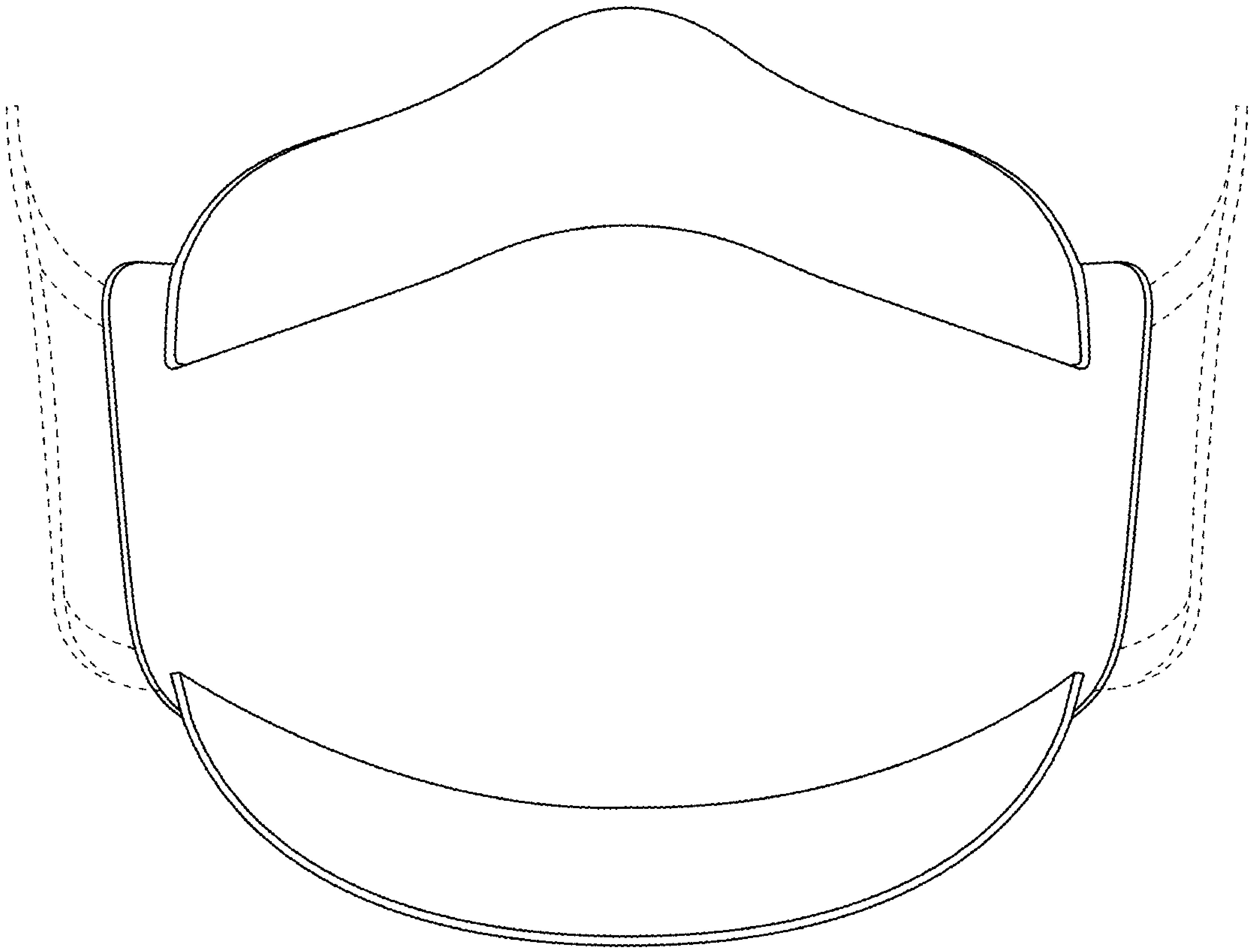

FIG. 10

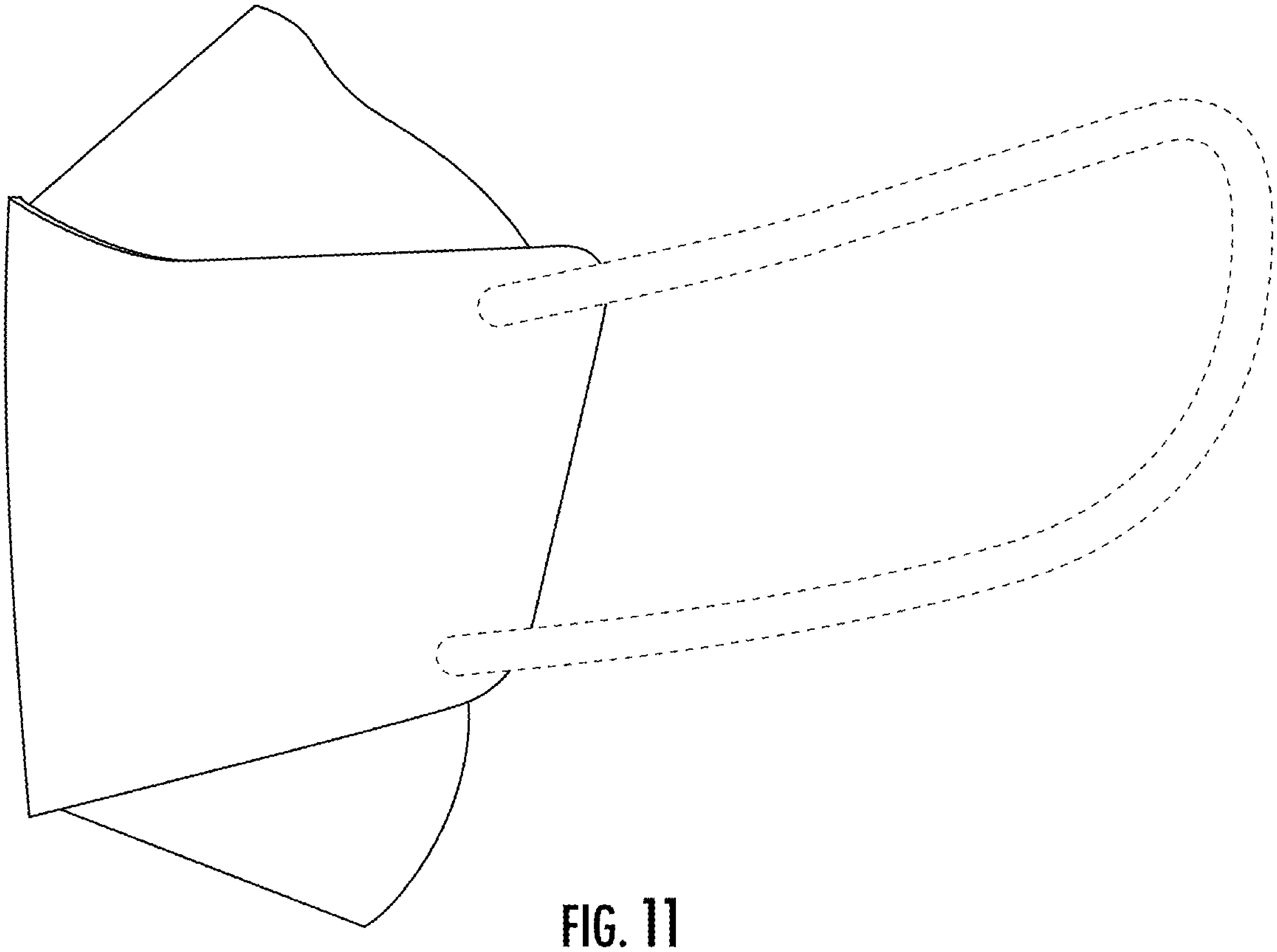

FIG. 11

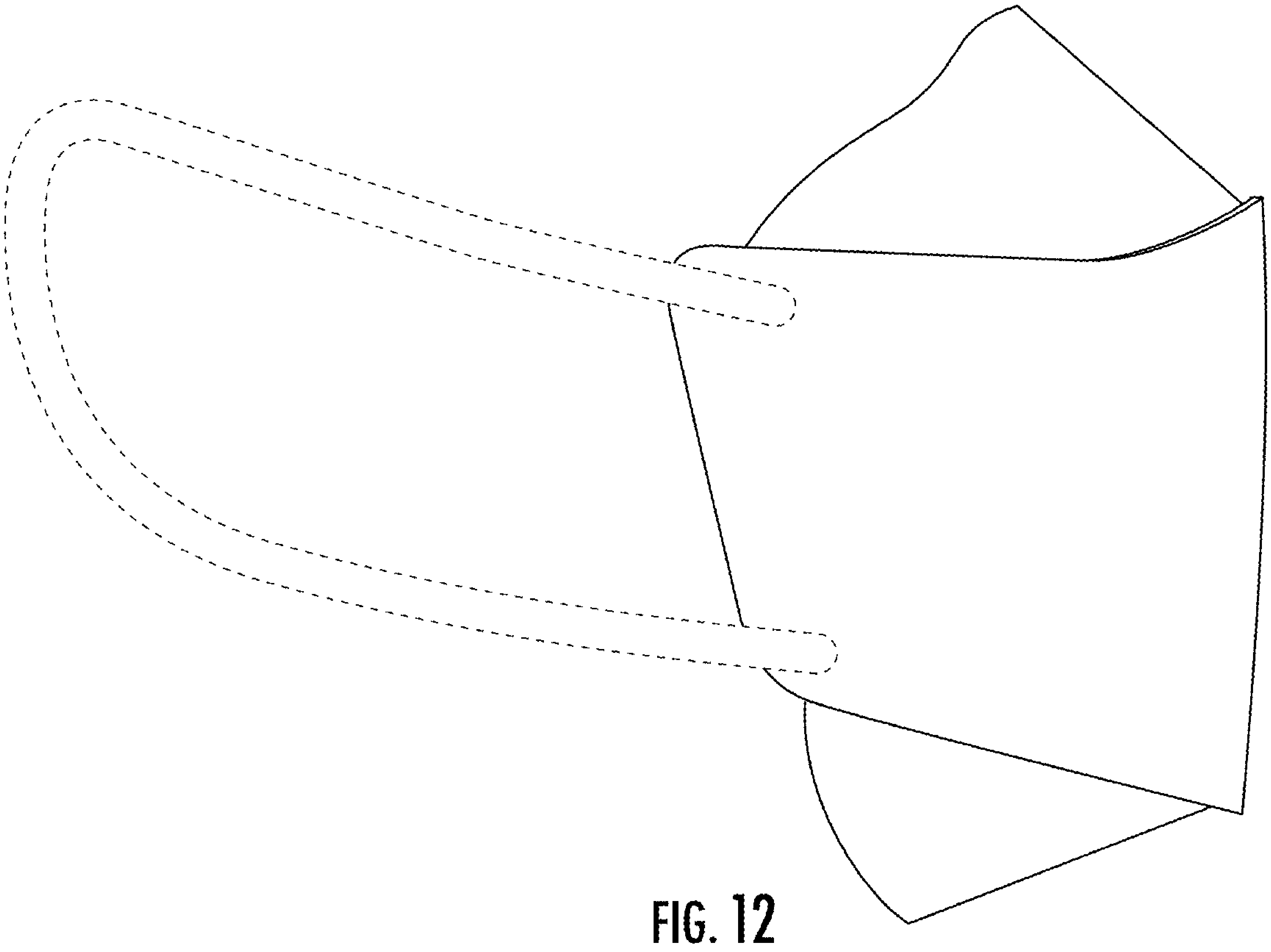

FIG. 12

FIG. 13

FIG. 14